

S/N 09/259,849



PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Paul A. Farrar

Examiner: Bernard E. Souw

Serial No.: 09/259,849

Group Art Unit: 2814

Filed: March 1, 1999

Docket: 303.557US1

Title: CONDUCTIVE STRUCTURES IN INTEGRATED CIRCUITS

**AMENDMENT AND RESPONSE UNDER 37 C.F.R. § 1.111**

Commissioner for Patents  
Washington, D.C. 20231

Applicant has reviewed the Office action mailed on September 28, 2000.

This response is accompanied by a petition, as well as the appropriate fee, to obtain a two-month extension of the time period for responding to the Office action, thereby moving the deadline for response from December 28, 2000 to February 28, 2000.

Please amend the above-identified patent application as follows.

**IN THE CLAIMS**

Please amend the claims as follows:

50. [Amended] A method of forming a conductor comprising:  
depositing an oxide layer over a planarized surface;  
etching a trench on the oxide layer;  
depositing a barrier layer of titanium on the oxide layer;  
depositing a seed layer of aluminum-copper on the barrier layer [oxide layer];  
removing the barrier layer and seed layer from selected areas or unused areas of the oxide  
layer, leaving a seed area; and  
depositing aluminum on the seed area.

54. [Amended] The method of claim 50, wherein depositing a seed layer of aluminum-copper [titanium] on the barrier layer [oxide layer] comprises:  
depositing the seed layer of aluminum-copper [titanium] on the barrier [oxide] layer by  
chemical vapor-deposition.

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